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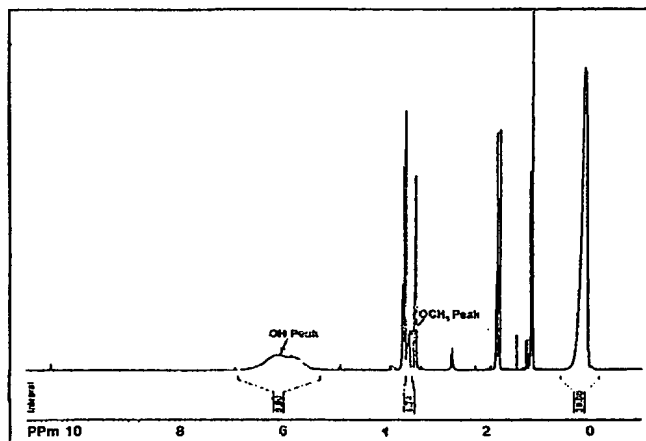
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(54) Title: COATING COMPOSITION FOR INSULATING FILM PRODUCTION, PREPARATION METHOD OF INSULATION FILM BY USING THE SAME, INSULATION FILM FOR SEMI-CONDUCTOR DEVICE PREPARED THEREFROM, AND SEMI-CONDUCTOR DEVICE COMPRISING THE SAME



(57) Abstract: The present invention relates to a coating composition for insulating film production, a preparation method of a low dielectric insulating film using the same, a low dielectric insulating film for a semiconductor device prepared therefrom, and a semiconductor device comprising the same, and more particularly to a coating composition for insulating film production having a low dielectric constant and that is capable of producing an insulating film with superior mechanical strength (elasticity), a preparation method of a low dielectric insulating film using the same, a low dielectric insulating film for a semiconductor device prepared therefrom, and a semiconductor device comprising the same. The coating composition of the present invention comprises an organic siloxane resin having a small molecular weight, and water, and significantly improves low dielectricity and mechanical strength of an insulating film.

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